

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of: Confirmation Number: 7419

FUKIAGE et al.

Application No.: 10/702,049 Group Art Unit: 1792

Filed: November 6, 2003 Examiner: Tadayyon Eslami, Tabassom

Title: METHOD OF IMPROVING POST-DEVELOP PHOTORESIST PROFILE ON
A DEPOSITED DIELECTRIC FILM

PRELIMINARY AMENDMENT WITH RCE

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

In response to the Advisory Action dated October 10, 2008, and the Final Office Action dated June 12, 2008, the due date for response to which has been extended to November 12, 2008 by the attached Petition for a Two Month Extension of Time and Fee, please amend the above-identified application as follows: